

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of

KOBAYASHI, S.

Atty. Ref.: 900-471

Appl. No. To be assigned

Group:

Filed: August 4, 2003

Examiner:

For: MASK PATTERN AND METHOD FOR FORMING RESIST PATTERN USING  
MASK PATTERN THEREOF

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August 4, 2003

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**PRELIMINARY AMENDMENT**

In order to place the above-identified application in better condition for  
examination, please amend the application as follows: